

AlGaAs Crystalline Coatings: Recent Progress and Future Prospects

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VCQ

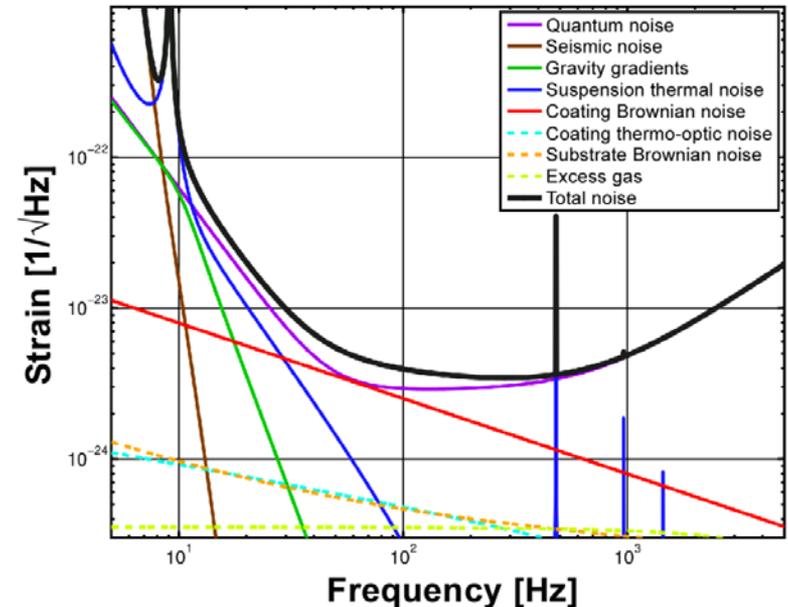
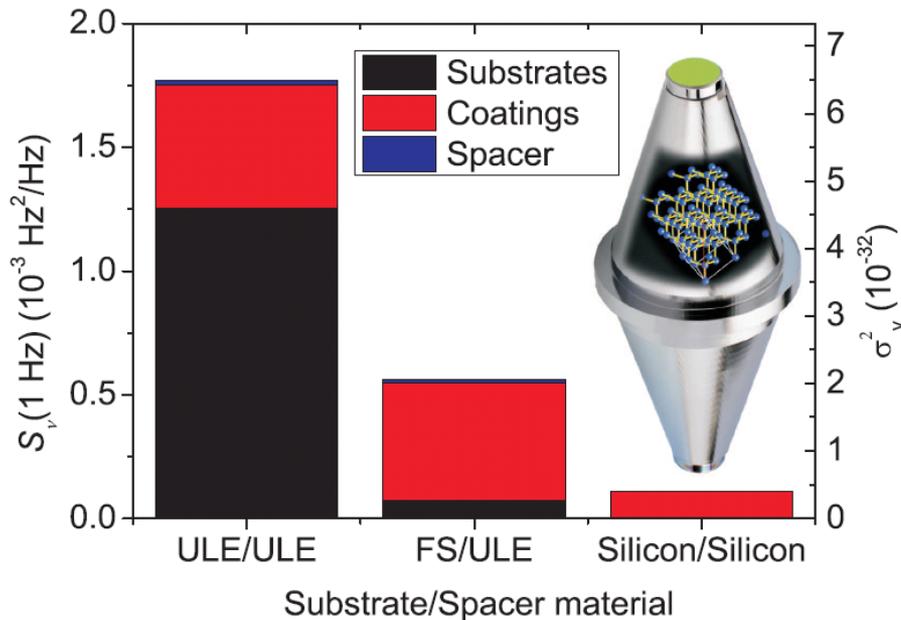


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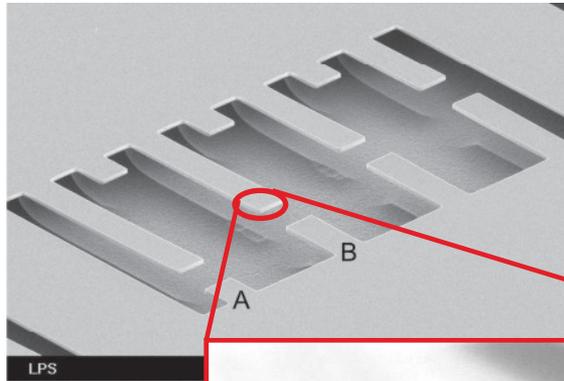
JILA
NIST/CU



Coating Thermal Noise Consequences

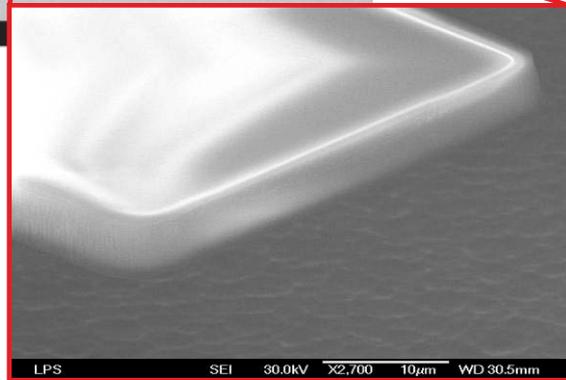


- State-of-the-art systems now (or will be) coating limited ($\text{Ta}_2\text{O}_5/\text{SiO}_2$)
 - from LSC studies by Crooks, Harry, Penn, etc. Ta_2O_5 is the culprit
 - titania doping enables a factor of ~ 2 improvement (loss angle: 2×10^{-4})
- Alternative solution to this vexing problem: *crystalline coatings!*
 - semiconductor industry has a long history with such materials systems



Dielectric Resonators

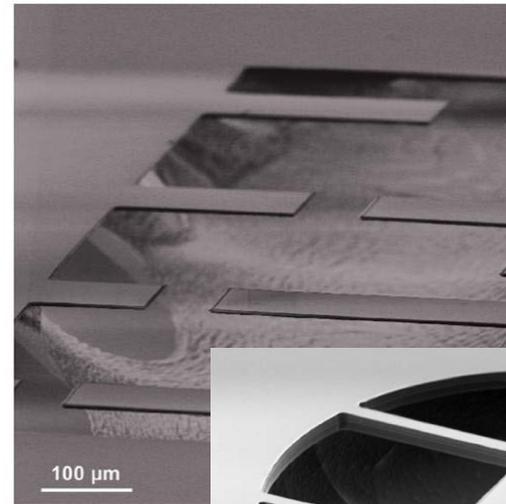
Collaboration with
Keith Schwab
(Cornell)



free-standing $\text{Ta}_2\text{O}_5/\text{SiO}_2$ HR coating

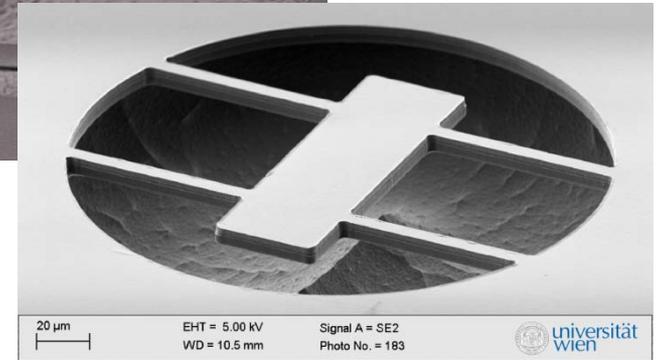
Reflectivity > 0.9999 , $Q \sim 2000 - 6000$
loss angle (Q^{-1}) similar to LIGO data

S. Gröblacher, S. Gigan, H. Böhm, A. Zeilinger, M. Aspelmeyer, Eur. Phys. Lett. 81, 54003 (2008)



Epitaxial AlGaAs Bragg Mirrors

FBH and Aspelmeyer
Group (UniVie)



free-standing epitaxial AlGaAs DBR

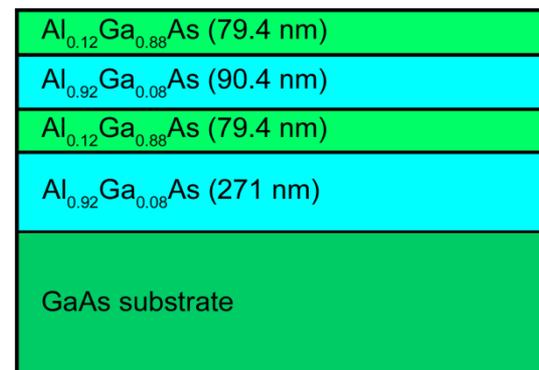
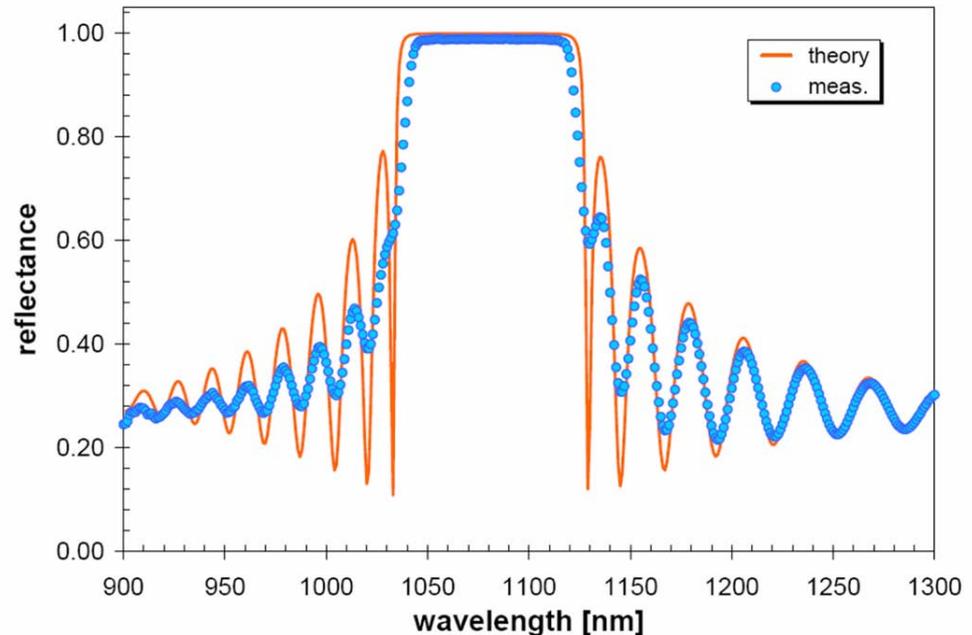
Reflectivity > 0.9999 , $Q \sim 2 \times 10^4 - 2 \times 10^5$
Significantly reduced damping, similar R

a) Cole, et al., Appl. Phys. Lett. 92, 261108 (2008)
b) G. D. Cole, Proc. SPIE. 8458-07 (2012)

AlGaAs Multilayer Details



- AlGaAs multilayer with varying Al content for index contrast
 - high index layers contain low Al content (0-12%)
 - 8% Ga incorporated in low index film to slow oxidation in ambient
- Potential for high reflectivity from ~ 650 nm – 3 μ m
 - measurements @ 1064 nm
- High quality epitaxy requires a lattice matched substrate
 - same crystalline symmetry
 - minimal deviation of lattice parameter (atomic spacing)

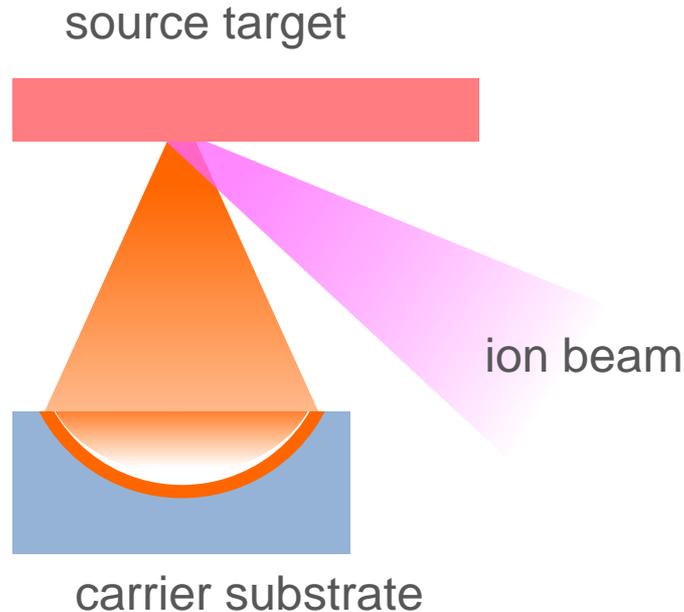


32 - 40x

1 μ m

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Ion Beam Sputtered Dielectric Films



State-of-the-art mirrors
alternating dielectric films,
typically $\text{Ta}_2\text{O}_5/\text{SiO}_2$

***Allows for deposition onto
essentially arbitrary
substrates***

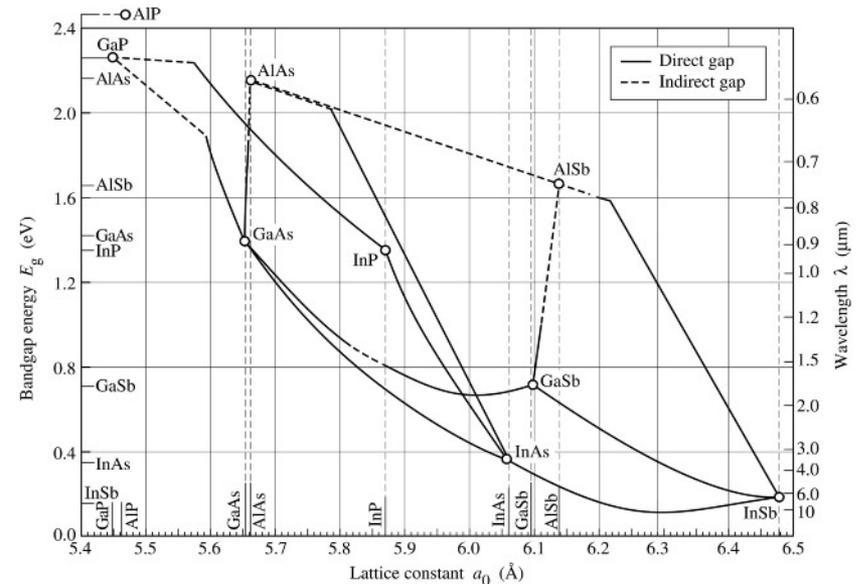
- Multilayer of amorphous films generated via ion beam sputtering
- Phenomenal optical properties (high R, low absorption and scatter)
- Flexible choice of substrates (assuming proper surface quality)
 - super-polished SiO_2 , Si, ULE, sapphire, etc.

Monocrystalline Mirrors



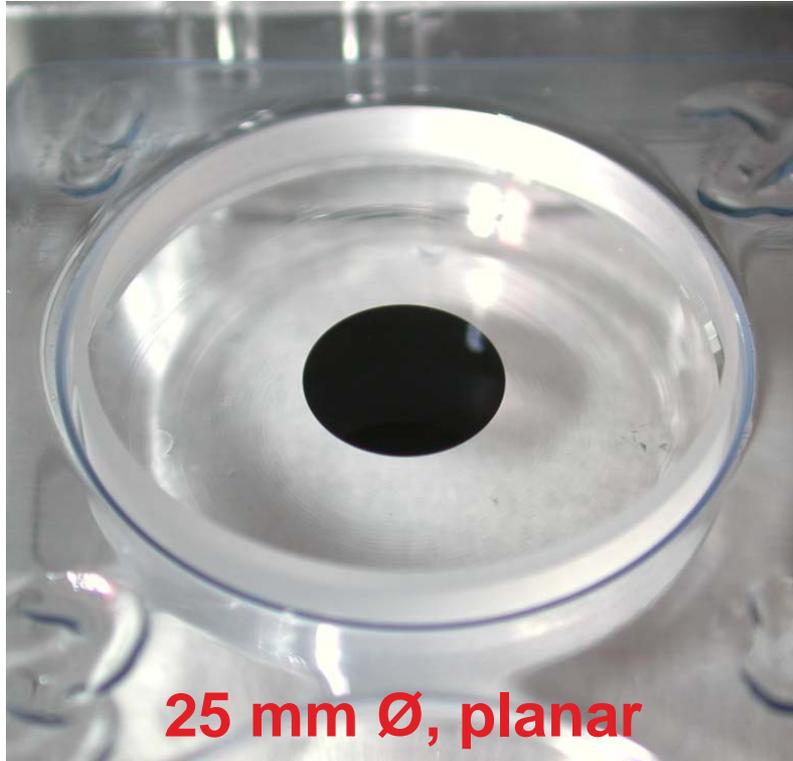
Ultra-low coating thermal noise
Macroscopic mirrors based on
epitaxial AlGaAs alloys

***Direct deposition onto
arbitrary substrates precluded
by lattice matching condition***

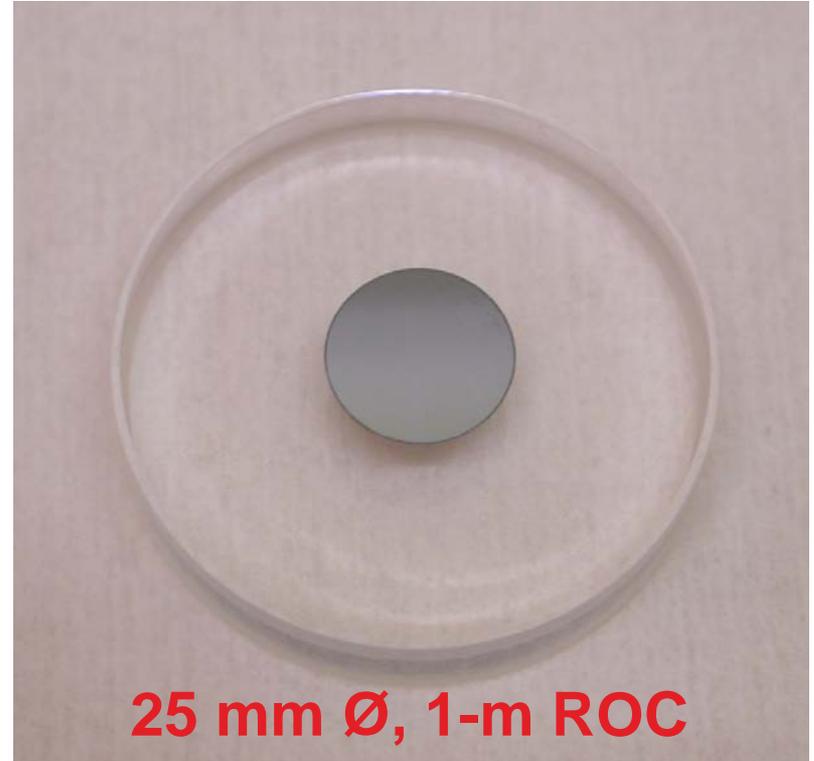


- Employ semiconductor microfabrication techniques to transfer AlGaAs multilayers onto arbitrary substrates (SiO_2 , sapphire, etc.)
 - ideal process allows for used of curved mirror blanks
 - identical form factor, no change in overall system design

Transferred Mirror Development



25 mm Ø, planar



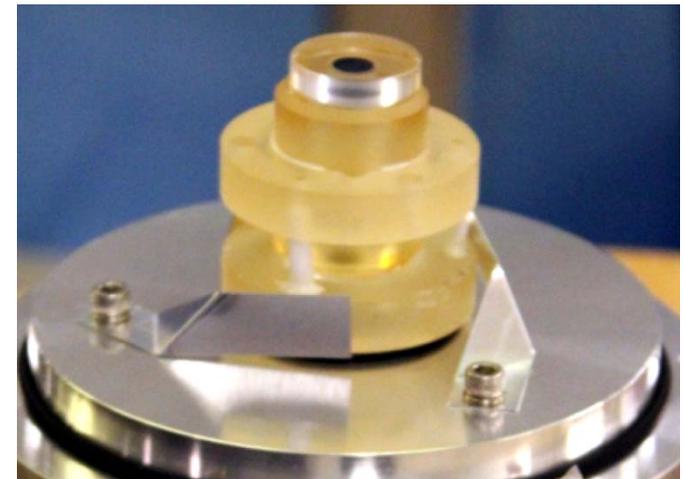
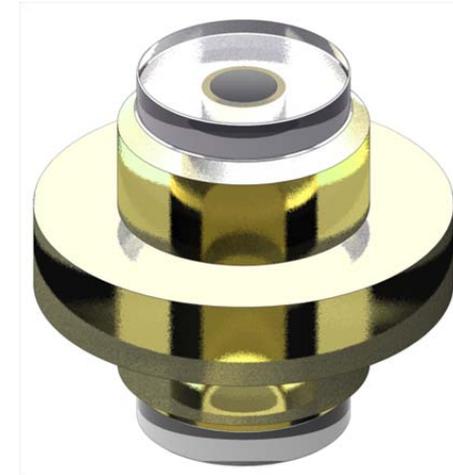
25 mm Ø, 1-m ROC

- Monocrystalline mirror discs transferred onto arbitrary substrates
 - temporary mounting and handling is the limiting process step
 - cleanliness is key to success, no voids or trapped particles!

Fixed-Spacer Reference Cavity



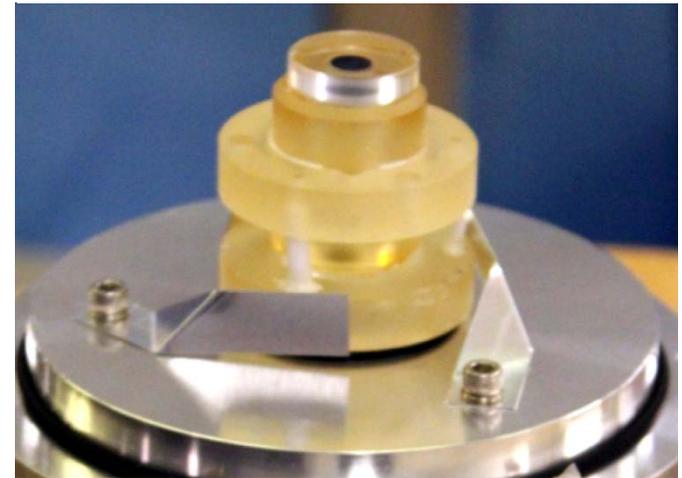
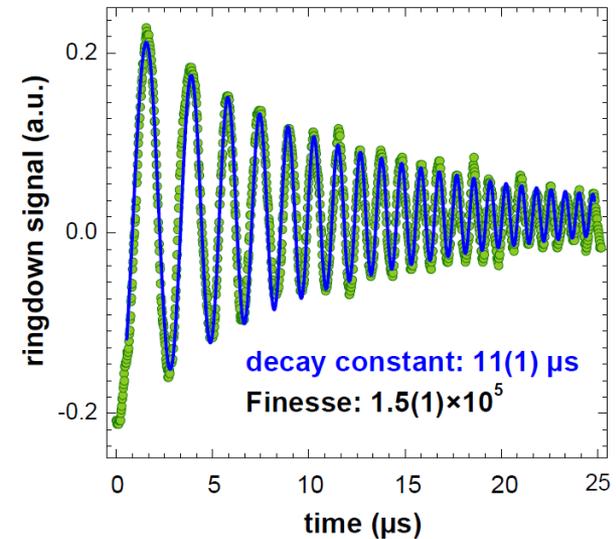
- Zerodur spacer with optically contacted AlGaAs-on-silica mirrors
 - short cavity length to accentuate mirror thermal noise effects
- Cavity mounted in a temperature controlled vacuum chamber
 - eliminate index variations and spacer thermal fluctuations
 - nodal support to minimize acceleration sensitivity
- Prototype and test-bed for opto-mechanical performance verification
 - cavity used for the construction of a stabilized laser at 1064 nm



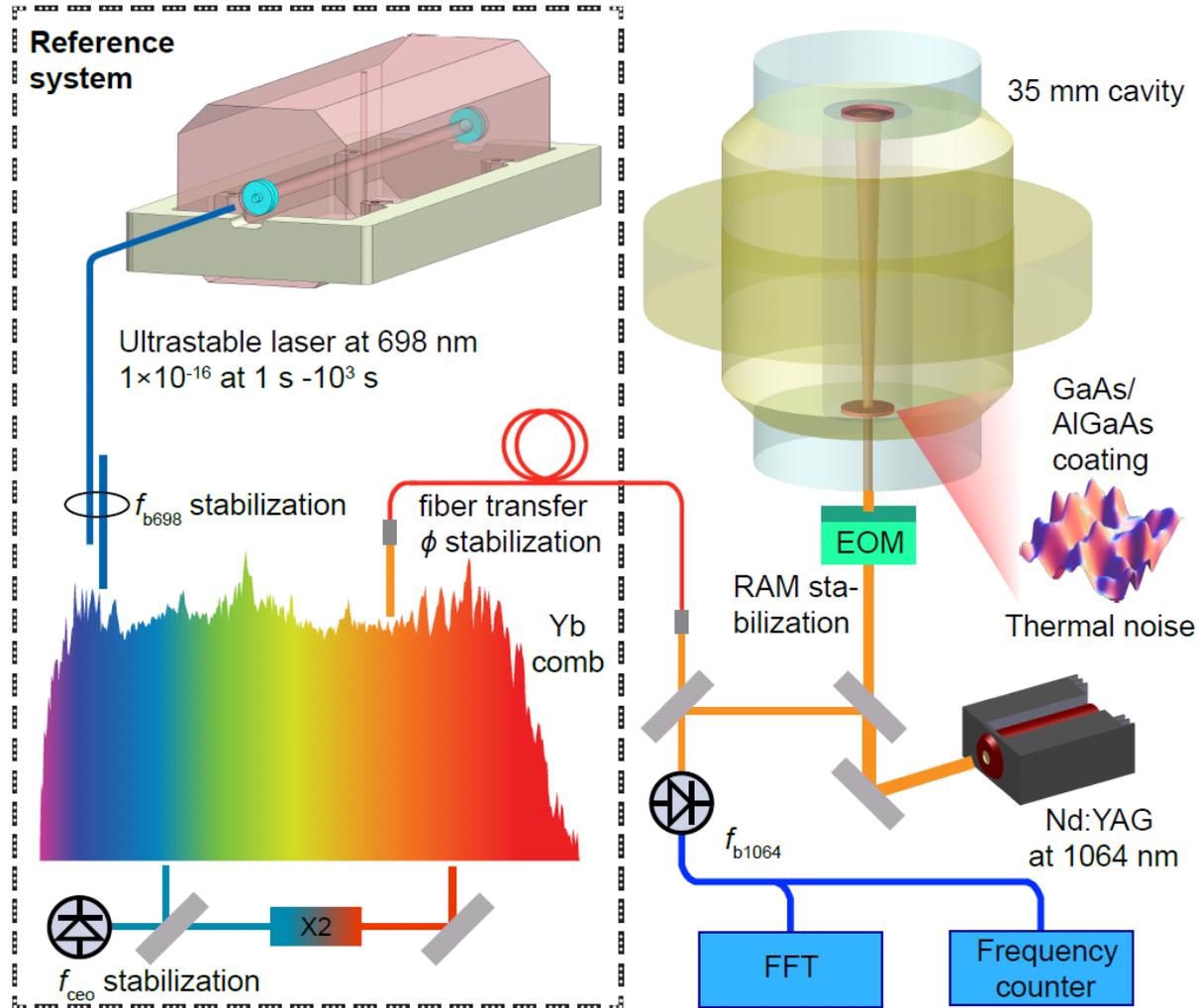
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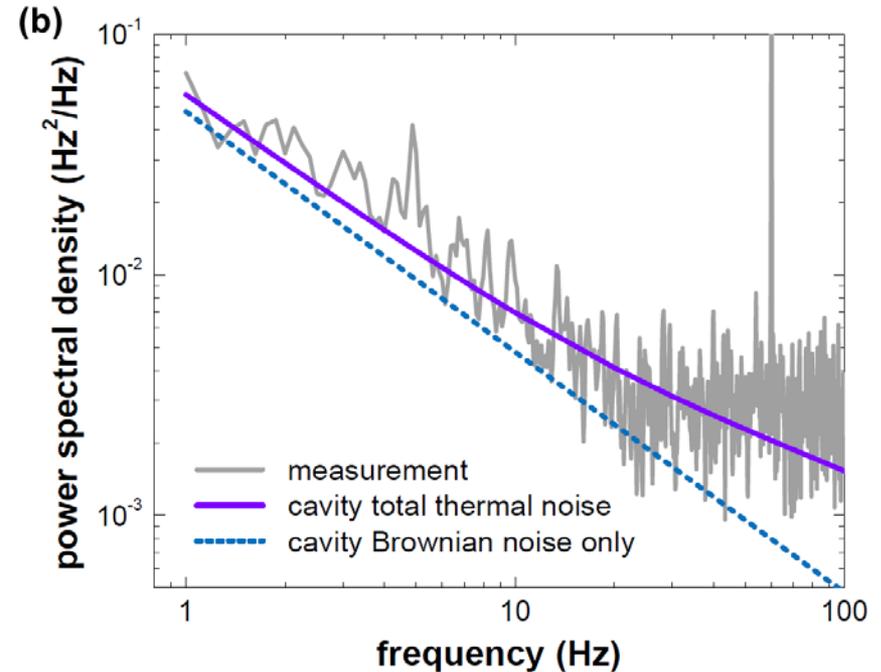
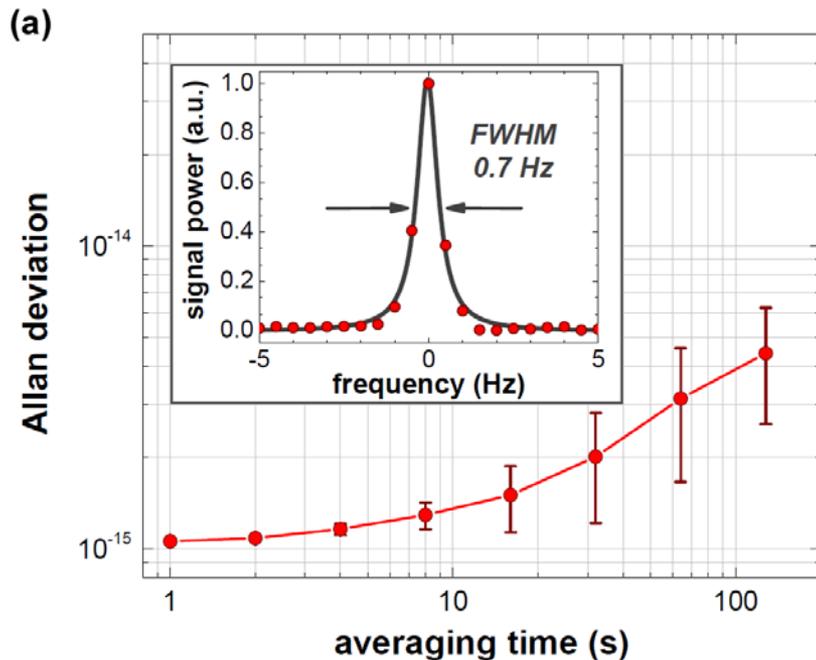
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Stabilized Laser Comparison

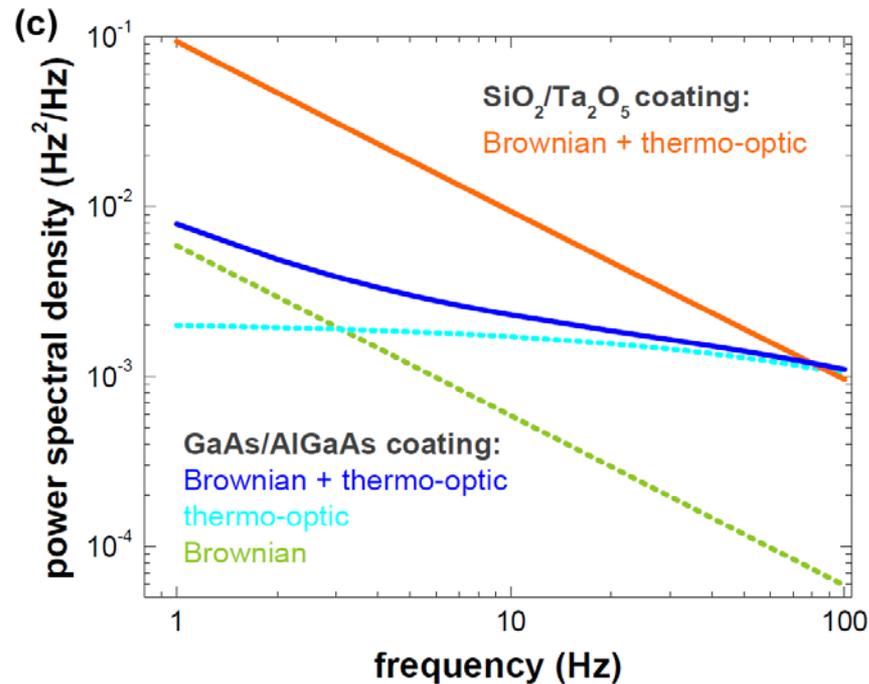


Thermal Noise Performance



- Allan deviation of $\sim 1 \times 10^{-15}$ at 1 s; linewidth of 700 mHz via FFT
 - long term stability limited by measurement setup and spacer
- Reference cavity noise measurement is thermally limited
 - fitted NPSD yields loss angle consistent with μ -resonators ($< 4 \times 10^{-5}$)

Thermo-Optic Noise



- Extracted quality factor matches measurements on μ -resonators
 - loss angle falls between 0 and 4×10^{-5} (depends on Q of fused silica)
- Excess thermo-optic noise anticipated at high frequencies
 - arises from thermoelastic + thermorefractive noise in crystalline AlGaAs

Summary of AlGaAs Mirror Properties

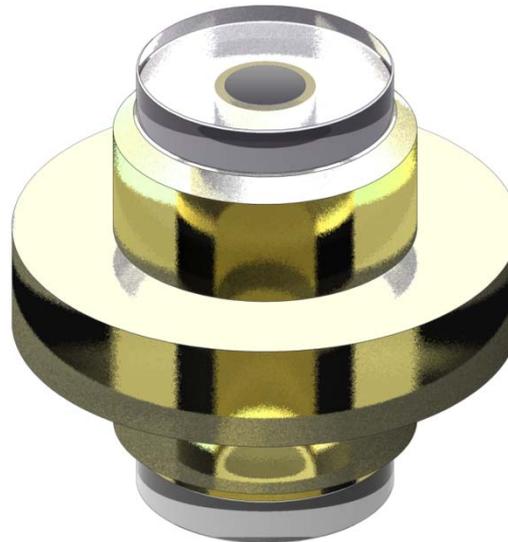


- We have realized tremendous progress in only 6 years, with the last ~ 2 being dedicated to cavity end mirrors
- Damping reduced by $10\text{-}100\times$ compared with dielectrics
 - room temperature Q-values $\sim 4\times 10^4$ ($\phi_{\text{RT}} \approx 2.5\times 10^{-5}$)
 - cryogenic Q $> 1\times 10^5$ ($\phi_{\text{min}} \approx 4.5\times 10^{-6}$) from 180 Hz to 4 MHz
 - compare with typical ϕ of $2\text{-}4\times 10^{-4}$ for $\text{Ta}_2\text{O}_5/\text{SiO}_2$ films
- Demonstrated low scatter loss and absorption
 - RMS surface roughness of 1.3 \AA RMS ($\sim 2 \text{ ppm}$ at 1064 nm)
 - absorption (probe limited) of 4.8 ppm (0.15 cm^{-1}) at 1064 nm
- Reflectivity $\gg 99.99\%$ measured for 40.5 layer pairs
 - highest measured finesse of $\sim 1.5\times 10^5$, potential for $\sim 10^6$

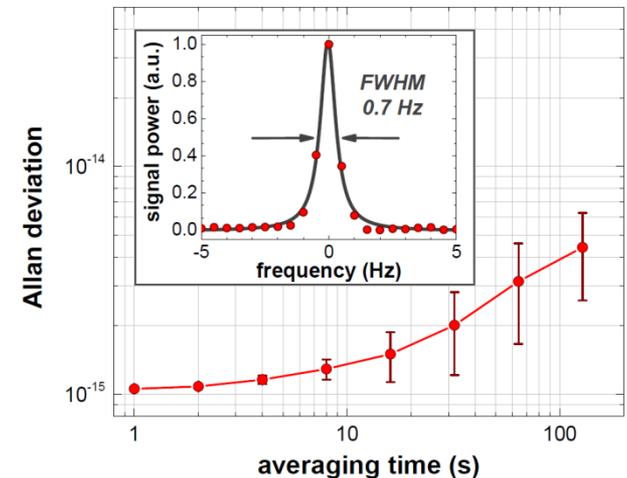
- ◆ Manufacturing low-noise substrate-transferred mirrors
 - used to construct ultra-narrow (<1 Hz) linewidth light sources
 - advanced optical atomic clocks, microwave generation, LIDAR/LADAR
 - next generation telecom frequency references and navigation systems



i) AlGaAs mirrors bonded to silica

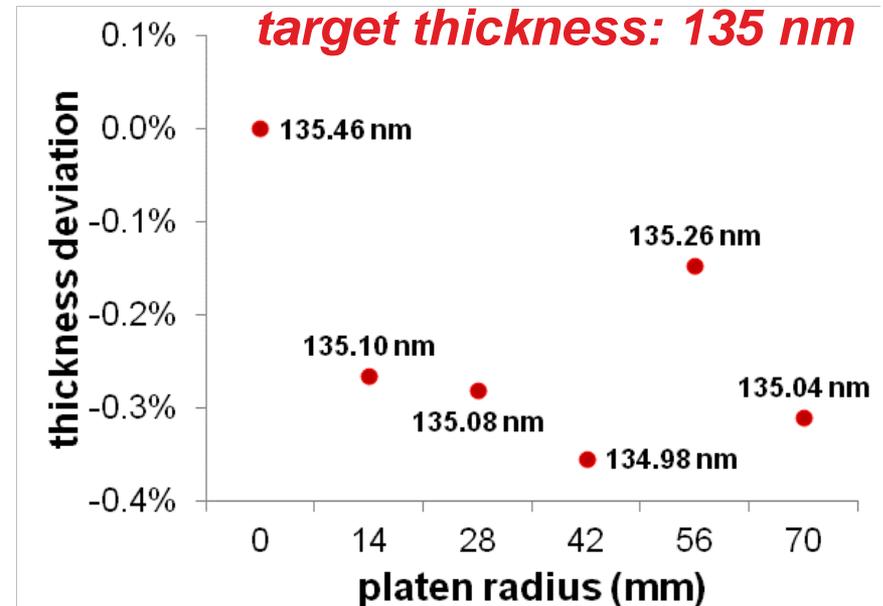
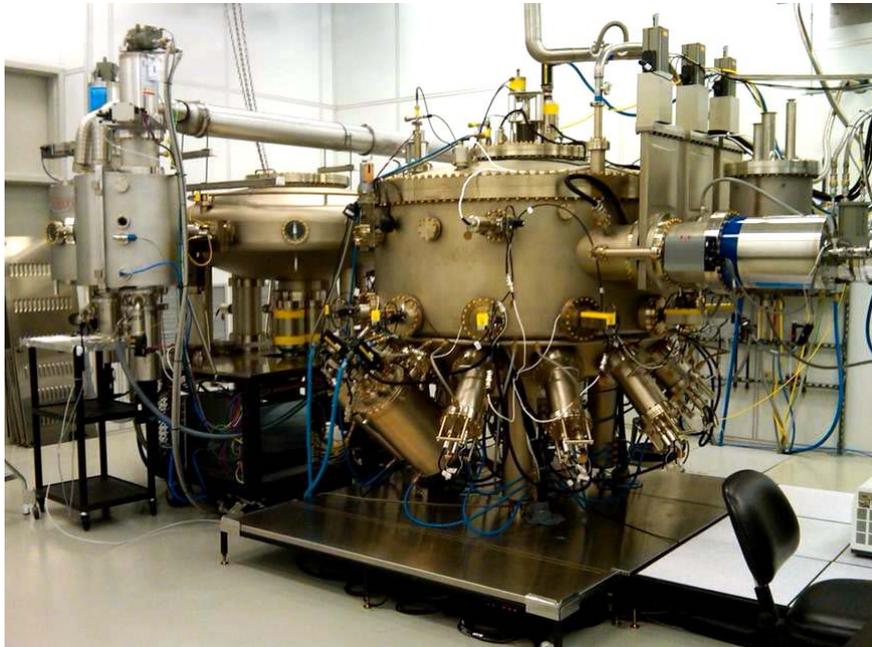


ii) mirrors used to construct a cavity



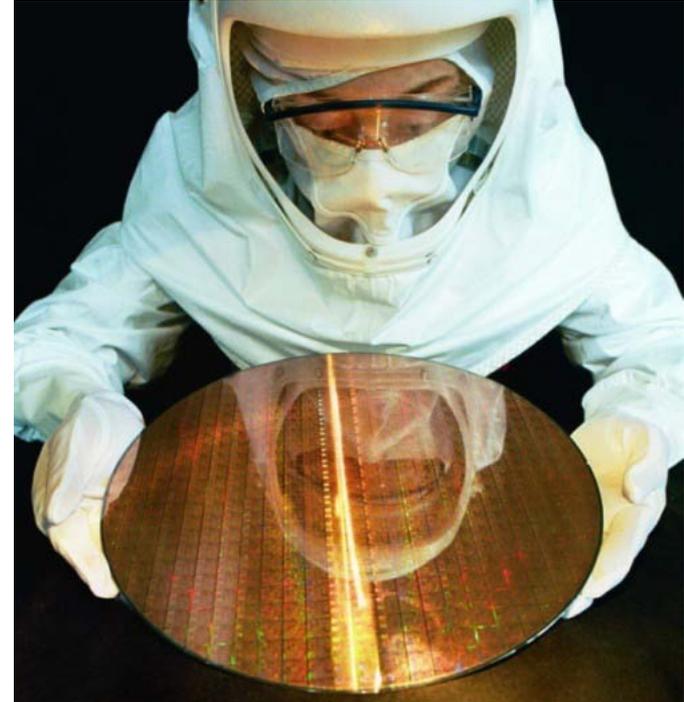
iii) cavity employed for laser stabilization

Large Area Crystal Growth



- Production MBE reactors for microwave electronics
 - 7 x 150-mm or 4 x 200-mm wafers (Veeco GEN2k/Riber R7k)
- Preliminary thickness uniformity test: excellent results
 - platen \emptyset is ~50 cm (current maximum GaAs wafer \emptyset of 200 mm)

Large Area Transferred Coatings



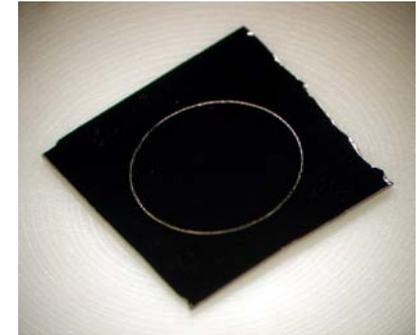
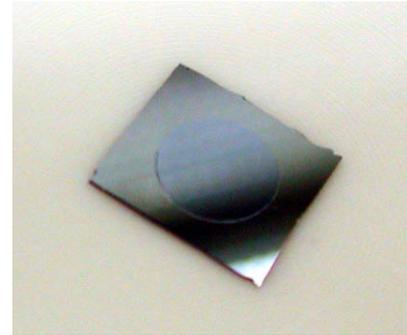
- Defect-free bonding demonstrated for 450-mm Ø wafers
 - commercial bonding system: EVG (St. Florian am Inn, Austria)
- All that is needed: custom tooling for thick substrates

Exploration of Alternative Substrates



- Direct-bonding process enables flexible integration of crystalline coatings onto essentially arbitrary substrates
- Optimized bonding conditions capable of bulk bond strength
 - O₂ plasma assisted bonding
 - in-situ ion cleaning (Mitsubishi)
- Relevant materials combinations have been explored for wafer-bonded micro/optoelectronics
 - AlGaAs on SiO₂ (room temp.)
 - AlGaAs on Al₂O₃ (50 mK)
 - AlGaAs on silicon (10 K)

GaAs/AlGaAs DBR on 111 Si

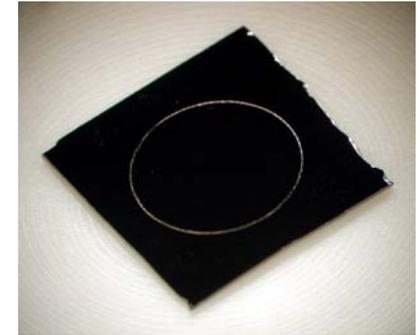
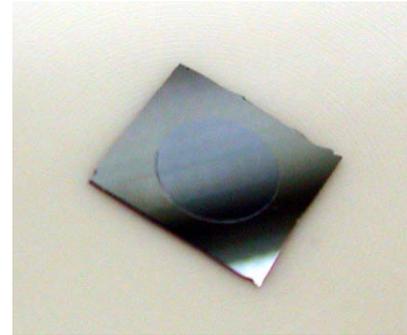


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